

Date: 03/05/2008

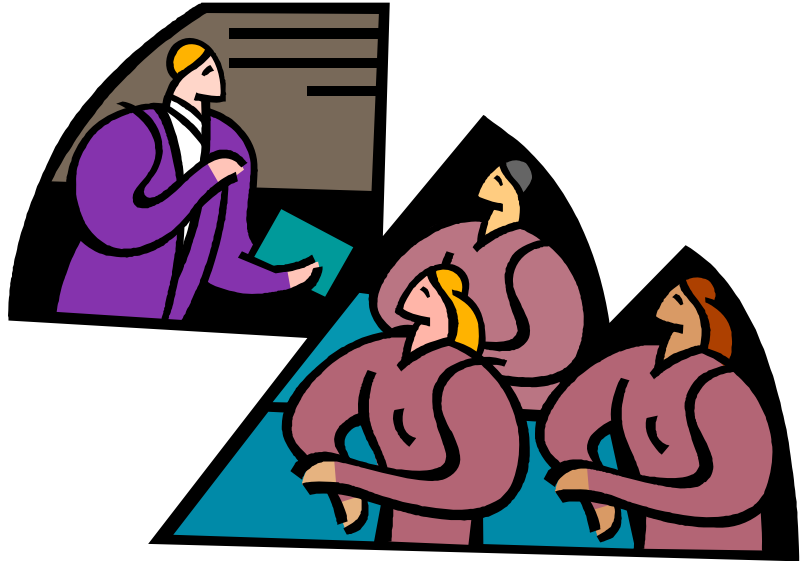
Time: 3:00 pm

Location:

Belknap Research Building
Room 139



Introduction to ELIONIX Electron Beam Lithography



The presentation will be an introduction to ELIONIX, a world-wide leading manufacturer of electron beam lithography and 3-D surface roughness measurement systems. The Elionix e-beam lithography product line, with 50kV, 80kV, and 100kV acceleration voltages has fine pattern writing capabilities below 8nm and a minimum electron beam diameter of 1.8nm. The overview will include, among other topics: discussion of stage stability, column design, sample introduction, and software capabilities. In addition, various EBL lithography applications, fine patterns, stitching accuracy, high versus low acceleration voltage images will be reviewed. Finally, a brief overview of Elionix 3D-SEM that allows for surface roughness measurements with a z-resolution of <3nm will be introduced. Questions are welcome at anytime during the presentation.

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